

IN THE ABSTRACT:

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

-- An exposure apparatus includes a chamber which incorporates an optical element and surrounds a predetermined region, a mechanism for setting an inert gas atmosphere in the chamber, and a closed vessel which surrounds the chamber. The purity of inert gas in the chamber is higher than a purity of inert gas in the closed vessel. --

IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 3, line 10, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

-- Only when gas replacement at a stagnation point at which gas hardly flows is progressed by molecular diffusion, does it take a very long time to decrease the concentration of gas present in the vessel from the beginning. --

Please substitute the paragraph beginning at page 5, line 15, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

-- The chamber desirably incorporates at least some of the optical elements of an illumination optical unit. --